

WHAT IS CLAIMED IS:

1. A piezoelectric element structure comprising:
a supporting substrate; and
a piezoelectric film supported on said supporting
5 substrate,

wherein said piezoelectric film contains a first,
layer, and a second layer having zirconium, each
provided with perovskite structure, and formed to be in
contact with each other or laminated through an
10 intermediate layer, and the temperature at the time of
thin film formation is 500°C or more to provide said
piezoelectric film, and for the formation thereof, a
quick cooling is given from the thin film formation
temperature at least to 450°C with a cooling speed of
15 30°C/min or more.

2. A piezoelectric element structure according to
Claim 1, wherein said first layer does not contain
zirconium.

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3. A piezoelectric element structure according to
Claim 2, wherein said intermediate layer is in contact
with said first layer and said second layer to reside
between these layers, and the zirconium concentration
25 increases inclinatorily.

4. A piezoelectric element structure according to

Claim 1, where the amount of zirconium content of said first layer is smaller than the amount of zirconium content of said second layer.

- 5 5. A liquid discharge recording head comprising:
 a main body portion provided with liquid discharge ports, and pressure chambers connected with said liquid discharge ports;
- 10 a piezoelectric film having lead, titanium, and zirconium; and
- 15 a piezoelectric vibrating portion provided partly for said pressure chambers containing electrodes arranged for both sides of said piezoelectric film, said vibrating portion being made to perform warping vibration to discharge recording liquid from said liquid discharge ports,
- 20 wherein said piezoelectric film contains a first layer having no zirconium, and a second layer having zirconium, each provided with perovskite structure, and formed to be in contact with each other, and the temperature at the time of thin film formation is 500°C or more to provide said piezoelectric film, and for the formation thereof, a quick cooling is given from the thin film formation temperature at least to 450°C with a cooling speed of 30°C/min or more.

- 25 6. A liquid discharge recording head comprising:

a main body portion provided with liquid discharge ports, and pressure chambers connected with said liquid discharge ports;

5 a piezoelectric film having lead, titanium, and zirconium; and

10 a piezoelectric vibrating portion provided partly for said pressure chambers containing electrodes arranged for both sides of said piezoelectric film, said vibrating portion being made to perform warping vibration to discharge recording liquid from said liquid discharge ports,

15 wherein said piezoelectric film contains a first layer and a second layer, each provided with perovskite structure, and formed to be in contact with each other, and the amount of zirconium content of said first layer is smaller than the amount of zirconium content of said second layer, and then, the temperature at the time of thin film formation is 500°C or more to provide said piezoelectric film, and for the formation thereof, a 20 quick cooling is given from the thin film formation temperature at least to 450°C with a cooling speed of 30°C/min or more.

7. A liquid discharge recording head comprising:

25 a main body portion provided with liquid discharge ports, and pressure chambers connected with said liquid discharge ports;

a piezoelectric film having lead, titanium, and zirconium; and

5 a piezoelectric vibrating portion provided partly for said pressure chambers containing electrodes arranged for both sides of said piezoelectric film, said vibrating portion being made to perform warping vibration to discharge recording liquid from said liquid discharge ports,

10 wherein said piezoelectric film contains a first layer having no zirconium, and a second layer having zirconium and an intermediate layer with the zirconium concentration thereof to be inclinatorily increased, each provided with perovskite structure, and formed to be in contact with each other, and the temperature at 15 the time of thin film formation is 500°C or more to provide said piezoelectric film, and for the formation thereof, a quick cooling is given from the thin film formation temperature at least to 450°C with a cooling speed of 30°C/min or more.

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8. A liquid discharge recording head according to Claim 5, wherein the ratio of zirconium/titanium in said second layer is set at 30/70 or more and 70/30 or less.

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9. A liquid discharge recording head according to Claim 5, wherein said piezoelectric film is mono-

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orientational crystal or monocrystal.

10. A liquid discharge recording head according
to Claim 5, wherein said piezoelectric film is formed
5 with orientation in the direction (100).

11. A liquid discharge recording head according
to Claim 5, wherein said piezoelectric film is
orientated in the direction (111), and the said
10 electrodes are comb-shaped or formed on the entire
face.

12. A liquid discharge recording head according
to Claim 5, wherein said piezoelectric film is formed
15 in a thickness of 10 μm or less.

13. A liquid discharge recording head according
to Claim 5, wherein said piezoelectric film is formed
in a thickness of 1 μm or more and 4 μm or less.
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14. A liquid discharge recording head according
to Claim 13, wherein the first layer of said
piezoelectric film is formed in a thickness of 30 nm or
more and 100 nm or less.
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15. A liquid discharge recording head according
to Claim 5, wherein said piezoelectric vibrating

portion is provided further with a vibrating plate.

16. A liquid discharge recording head according
to Claim 15, wherein said vibrating plate is formed by
5 at least one of materials or a laminated member of the
materials selected from nickel, chromium, aluminum,
titanium, zirconium, and from the group of oxide
thereof or nitride thereof, silicon, silicon oxide,
polymer organic materials, and YSZ.
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17. A liquid discharge recording head according
to Claim 15, wherein said vibrating plate is formed
with the vibrating plate characteristics by ion
injection on the upper part of the main body substrate
15 to form pressure chambers.

18. A liquid discharge recording head according
to Claim 15, wherein said vibrating plate is formed on
a silicon monocrystal substrate with epitaxial
development.
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19. A liquid discharge recording head according
to Claim 5, wherein the second layer of said
piezoelectric film contains niobium and tin, manganese,
25 and provides antiferroelectricity.

20. A liquid discharge recording head according

to Claim 5, wherein the electrode layers arranged for both side of said piezoelectric film are formed by platinum, iridium, conductive oxide, or conductive nitride.

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21. A liquid discharge recording head according to Claim 5, wherein said main body portion is provided with a plurality of liquid discharge ports, and a plurality of said pressure chambers corresponding to each of liquid discharge ports, respectively, and from the electrodes arranged for both sides of said piezoelectric film, at least those on one side are separated for installation corresponding to said pressure chambers in order to structure the piezoelectric vibrating portion for each pressure chamber.

22. A liquid discharge recording head according to Claim 21, wherein said piezoelectric film is separated to be arranged corresponding to said pressure chambers, and the electrodes on one side are formed on each of said separated piezoelectric film.

23. A liquid discharge recording head according to Claim 5, wherein the circumference of said piezoelectric vibrating portion is directly connected with the circumference of the pressure chamber without

using bonding agent ~~or~~ the like.

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Sub A1*
24. A method for manufacturing a liquid discharge recording head provided with the main body portion having liquid discharge ports, and pressure chambers with opening portion on part thereof, being connected with said liquid discharge ports, and piezoelectric vibrating portion installed to close said opening portion, comprising the following steps of:

10 forming vibrating plate and electrode on a substrate;

forming on said electrode a first layer having perovskite structure containing lead and titanium, and setting a temperature of 500°C or more when forming on said first layer a second layer having perovskite structure containing zirconium, lead, and titanium, and then, giving quick cooling from said temperature at least to 450°C with cooling speed of 30°C/min or more for forming piezoelectric film containing said first layer and second layer;

separating said piezoelectric film after the formation of said piezoelectric film corresponding to pressure chambers;

25 forming the upper electrode, and pressure chambers corresponding said separated piezoelectric films; and bonding a nozzle plate having liquid discharge ports formed therefor,

wherein in the step of forming said piezoelectric film, said first layer is formed so as not to contain zirconium or so as to make the amount of contained zirconium smaller than that of said second layer.

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25. A method for manufacturing a liquid discharge recording head provided with the main body portion having liquid discharge ports, and pressure chambers with opening portion on part thereof, being connected 10 with said liquid discharge ports, and piezoelectric vibrating portion installed to close said opening portion, comprising the following steps of:

forming on a supporting substrate a first layer having perovskite structure containing lead and 15 titanium, and setting a temperature of 500°C or more when forming on said first layer a second layer having perovskite structure containing zirconium, lead, and titanium, and then, giving quick cooling from said temperature at least to 450°C with cooling speed of 20 30°C/min or more for forming piezoelectric film containing said first layer and second layer, and forming on said supporting substrate the piezoelectric vibrating portion having said piezoelectric film;

bonding without using adhesive agent the 25 circumference of said opening portion of said main body portion with the circumference of said piezoelectric vibrating portion by arranging them to be faced; and

removing said supporting substrate subsequent to
said step,

wherein in the step of forming said piezoelectric
vibrating portion, said first layer is formed so as not
5 to contain zirconium or so as to make the amount of
contained zirconium smaller than that of said second
layer.

26. A method for manufacturing a liquid discharge
10 recording head according to claim 25, wherein said
first layer, second layer, vibrating plate, and
electrode are formed by the vapor method including
sputtering and CVD method.

15 27. A method for manufacturing a liquid discharge
recording head according to Claim 24, wherein a silicon
substrate is used as said substrate, and said substrate
is removed by etching using a mixed acid of
hydrochloric acid and nitric acid to make the interior
20 thereof pressure chambers.

28. A method for manufacturing a liquid discharge recording head according to Claim 27, wherein said substrate is removed by etching using hydrofluoric acid solution or potassium hydroxide solution.

29. A liquid discharge recording head according

to Claim 6, wherein the ratio of zirconium/titanium in said second layer is set at 30/70 or more and 70/30 or less.

5 30. A liquid discharge recording head according to Claim 6, wherein said piezoelectric film is mono-orientational crystal or monocrystal.

10 31. A liquid discharge recording head according to Claim 6, wherein said piezoelectric film is formed with orientation in the direction (100).

15 32. A liquid discharge recording head according to Claim 6, wherein said piezoelectric film is orientated in the direction (111), and the said electrodes are comb-shaped or formed on the entire face.

20 33. A liquid discharge recording head according to Claim 6, wherein said piezoelectric film is formed in a thickness of 10 μm or less.

25 34. A liquid discharge recording head according to Claim 6, wherein said piezoelectric film is formed in a thickness of 1 μm or more and 4 μm or less.

35. A liquid discharge recording head according

to Claim 7, wherein the ratio of zirconium/titanium in said second layer is set at 30/70 or more and 70/30 or less.

5 36. A liquid discharge recording head according to Claim 7, wherein said piezoelectric film is mono-orientational crystal or monocrystal.

10 37. A liquid discharge recording head according to Claim 7, wherein said piezoelectric film is formed with orientation in the direction (100).

15 38. A liquid discharge recording head according to Claim 7, wherein said piezoelectric film is orientated in the direction (111), and the said electrodes are comb-shaped or formed on the entire face.

20 39. A liquid discharge recording head according to Claim 7, wherein said piezoelectric film is formed in a thickness of 10 μm or less.

25 40. A liquid discharge recording head according to Claim 8, wherein said piezoelectric film is formed in a thickness of 1 μm or more and 4 μm or less.

41. A liquid discharge recording head according

to Claim 29, wherein the first layer of said piezoelectric film is formed in a thickness of 30 nm or more and 100 nm or less.

5 42. A liquid discharge recording head according to Claim 35, wherein the first layer of said piezoelectric film is formed in a thickness of 30 nm or more and 100 nm or less.

10 43. A liquid discharge recording head according to Claim 6, wherein said piezoelectric vibrating portion is provided further with a vibrating plate.

15 44. A liquid discharge recording head according to Claim 7, wherein said piezoelectric vibrating portion is provided further with a vibrating plate.

20 45. A liquid discharge recording head according to Claim 43, wherein said vibrating plate is formed by at least one of materials or a laminated member of the materials selected from nickel, chromium, aluminum, titanium, zirconium, and from the group of oxide thereof or nitride thereof, silicon, silicon oxide, polymer organic materials, and YSZ.

25 46. A liquid discharge recording head according to Claim 44, wherein said vibrating plate is formed by

at least one of materials or a laminated member of the
materials selected from nickel, chromium, aluminum,
titanium, zirconium, and from the group of oxide
thereof or nitride thereof, silicon, silicon oxide,
5 polymer organic materials, and YSZ.

47. A liquid discharge recording head according
to Claim 43, wherein said vibrating plate is formed
with the vibrating plate characteristics by ion
10 injection on the upper part of the main body substrate
to form pressure chambers.

48. A liquid discharge recording head according
to Claim 44, wherein said vibrating plate is formed
15 with the vibrating plate characteristics by ion
injection on the upper part of the main body substrate
to form pressure chambers.

49. A liquid discharge recording head according
20 to Claim 43, wherein said vibrating plate is formed on
a silicon monocrystal substrate with epitaxial
development.

50. A liquid discharge recording head according
25 to Claim 44, wherein said vibrating plate is formed on
a silicon monocrystal substrate with epitaxial
development.

51. A liquid discharge recording head according to Claim 6, wherein the second layer of said piezoelectric film contains niobium and tin, manganese, and provides antiferroelectricity.

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52. A liquid discharge recording head according to Claim 6, wherein the electrode layers arranged for both side of said piezoelectric film are formed by platinum, iridium, conductive oxide, or conductive nitride.

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53. A liquid discharge recording head according to Claim 6, wherein said main body portion is provided with a plurality of liquid discharge ports, and a plurality of said pressure chambers corresponding to each of liquid discharge ports, respectively, and from the electrodes arranged for both sides of said piezoelectric film, at least those on one side are separated for installation corresponding to said pressure chambers in order to structure the piezoelectric vibrating portion for each pressure chamber.

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54. A liquid discharge recording head according to Claim 7 wherein the second layer of said piezoelectric film contains niobium and tin, manganese, and provides antiferroelectricity.

55. A liquid discharge recording head according
to Claim 7, wherein the electrode layers arranged for
both side of said piezoelectric film are formed by
platinum, iridium, conductive oxide, or conductive
5 nitride.

56. A liquid discharge recording head according
to Claim 7, wherein said main body portion is provided
with a plurality of liquid discharge ports, and a
10 plurality of said pressure chambers corresponding to
each of liquid discharge ports, respectively, and from
the electrodes arranged for both sides of said
piezoelectric film, at least those on one side are
separated for installation corresponding to said
15 pressure chambers in order to structure the
piezoelectric vibrating portion for each pressure
chamber.

57. A liquid discharge recording head according
20 to Claim 53, wherein said piezoelectric film is
separated to be arranged corresponding to said pressure
chambers, and the electrodes on one side are formed on
each of said separated piezoelectric film.

25 58. A liquid discharge recording head according
to Claim 56, wherein said piezoelectric film is
separated to be arranged corresponding to said pressure

chambers, and the electrodes on one side are formed on each of said separated piezoelectric film.

59. A liquid discharge recording head according
5 to Claim 6, wherein the circumference of said
piezoelectric vibrating portion is directly connected
with the circumference of the pressure chamber without
using bonding agent or the like.

10 60. A liquid discharge recording head according
to Claim 7, wherein the circumference of said
piezoelectric vibrating portion is directly connected
with the circumference of the pressure chamber without
using bonding agent or the like.

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